

L Number	Hits	Search Text	DB	Time stamp
1	209	("stacked capacitor" or "stack capacitor") and ((oxygen and (nitrogen or argon)) SAME (thermal or anneal or annealing or RTP or RTA))	USPAT; US-PGPUB	2002/10/20 15:58
2	60	((("stacked capacitor" or "stack capacitor") and ((oxygen and (nitrogen or argon)) SAME (thermal or anneal or annealing or RTP or RTA))) and bst	USPAT; US-PGPUB	2002/10/20 15:31
3	31	((("stacked capacitor" or "stack capacitor") and ((oxygen and (nitrogen or argon)) SAME (thermal or anneal or annealing or RTP or RTA))) and bst) and (Ru or ruthenium)	USPAT; US-PGPUB	2002/10/20 15:31
4	58	capacitor with (anneal or annealing or anneald) with (improve or improving)	USPAT; US-PGPUB	2002/10/20 15:59
5	17	(capacitor with (anneal or annealing or anneald) with (improve or improving)) and ruthenium	USPAT; US-PGPUB	2002/10/20 15:59
10	24	((("in situ" or insitu) WITH (plug or contact or hole)) and ("stacked capacitor" or "stack capacitor")	USPAT; US-PGPUB	2002/10/20 17:32
11	24	((("in situ" or insitu) WITH (plug or contact or hole)) and ("stacked capacitor" or "stack capacitor")) and ("doped" with (polysilicon or poly))	USPAT; US-PGPUB	2002/10/20 17:31
12	16	((("in situ" or insitu) WITH (plug or contact or hole)) and ("stacked capacitor" or "stack capacitor")) and ("doped" with (polysilicon or poly))) and (cvd or "chemical vapor")	USPAT; US-PGPUB	2002/10/20 17:27
13	8	((("in situ" or insitu) WITH (plug or contact or hole)) and ("stack capacitor")	USPAT; US-PGPUB	2002/10/20 17:32
14	50	((("in situ" or insitu) WITH (plug or contact or hole)) and (capacitor)	USPAT; US-PGPUB	2002/10/20 18:50
16	28	((US-6455424-\$ or US-6255187-\$ or US-6159868-\$ or US-6010931-\$ or US-5668040-\$ or US-6091099-\$ or US-6281142-\$ or US-5998225-\$ or US-6274454-\$ or US-6265262-\$ or US-6338996-\$ or US-6146968-\$).did.).p64-p128. or ((US-20020022357-\$ or US-20010024852-\$ or US-20020102826-\$ or US-20020096745-\$ or US-20020076878-\$ or US-20010053058-\$ or US-20010052466-\$ or US-20010016382-\$ or US-20010006838-\$ or US-20010043453-\$ or US-20020037624-\$ or US-20020037630-\$ or US-20020022334-\$ or US-20010029113-\$ or US-20010009282-\$ or US-20020019109-\$ or US-20010039097-\$ or US-20010012698-\$).did.).p129-p134.) and (cvd or "chemical vapor")	USPAT; US-PGPUB	2002/10/20 17:41

17	28	((US-6455424-\$ or US-6255187-\$ or US-6159868-\$ or US-6010931-\$ or US-5668040-\$ or US-6091099-\$ or US-6281142-\$ or US-5998225-\$ or US-6274454-\$ or US-6265262-\$ or US-6338996-\$ or US-6146968-\$).did.).p64-p128. or ((US-20020022357-\$ or US-20010024852-\$ or US-20020102826-\$ or US-20020096745-\$ or US-20020076878-\$ or US-20010053058-\$ or US-20010052466-\$ or US-20010016382-\$ or US-20010006838-\$ or US-20010043453-\$ or US-20020037624-\$ or US-20020037630-\$ or US-20020022334-\$ or US-20010029113-\$ or US-20010009282-\$ or US-20020019109-\$ or US-20010039097-\$ or US-20010012698-\$).did.).p129-p134.) and (cvd or "chemical vapor" or pvd or "physical vapor")	USPAT; US-PGPUB	2002/10/20 17:47
18	90	((TiN or TiAlN) WITH (cvd or "chemical vapor" or pvd or "physical vapor")) SAME (contact or hole or recess or trench)) and ("stack capacitor" or "stacked capacitor")	USPAT; US-PGPUB	2002/10/20 17:48
21	1	"6211035".PN.	USPAT	2002/10/20 17:52
22	0	6265262.URPN.	USPAT	2002/10/20 17:54
23	48831	"50" and (cvd or "chemical vapor")	USPAT; US-PGPUB	2002/10/20 18:50
-	1394	(ruthenium or Ru) with (ammonia or ammonium or "NH.sub.3" or "N.sub.2O")	USPAT; US-PGPUB	2002/10/03 09:50
-	226	((ruthenium or Ru) with (ammonia or ammonium or "NH.sub.3" or "N.sub.2O")) same (oxidizing or oxidation or oxidize or oxidized)	USPAT; US-PGPUB	2002/10/03 09:44
-	23	((ruthenium or Ru) with (ammonia or ammonium or "NH.sub.3" or "N.sub.2O")) same (oxidizing or oxidation or oxidize or oxidized) SAME (capacitor or node or plate or electrode)	USPAT; US-PGPUB	2002/10/03 09:43
-	3	((ruthenium or Ru) with (ammonia or ammonium or "NH.sub.3" or "N.sub.2O")) and bst	USPAT; US-PGPUB	2002/10/03 09:44
-	2631	(ruthenium or Ru) same (ammonia or ammonium or "NH.sub.3" or "N.sub.2O")	USPAT; US-PGPUB	2002/10/03 09:50
-	23	((ruthenium or Ru) same (ammonia or ammonium or "NH.sub.3" or "N.sub.2O")) and BST	USPAT; US-PGPUB	2002/10/03 12:14
-	110	(ruthenium or Ru) with (rough or roughness or smooth or smoothness)	USPAT; US-PGPUB	2002/10/03 11:00
-	15	((ruthenium or Ru) with (rough or roughness or smooth or smoothness)) and bst	USPAT; US-PGPUB	2002/10/03 11:03
-	2	("5728603" "5853500").PN.	USPAT	2002/10/03 12:05
-	0	6159868.URPN.	USPAT	2002/10/03 12:06
-	5	("5293510" "5466629" "5486713" "5717236" "5801105").PN.	USPAT	2002/10/03 12:06
-	178	((ruthenium or Ru) and (ammonia or ammonium or "NH.sub.3" or "N.sub.2O")) and BST	USPAT; US-PGPUB	2002/10/04 11:34
-	635	(438/240).CCLS.	USPAT; US-PGPUB	2002/10/03 16:09
-	1449	(438/253).CCLS.	USPAT; US-PGPUB	2002/10/03 16:09
-	1496	(438/396).CCLS.	USPAT; US-PGPUB	2002/10/03 16:09
-	128	((438/253).CCLS.) and ruthenium	USPAT; US-PGPUB	2002/10/03 16:12
-	165	((438/396).CCLS.) and ruthenium	USPAT; US-PGPUB	2002/10/03 16:10
-	167	((438/240).CCLS.) and ruthenium	USPAT; US-PGPUB	2002/10/03 16:10

-	121	((((438/253).CCLS.) and ruthenium) or ((438/396).CCLS.) and ruthenium) or ((438/240).CCLS.) and ruthenium)) and (ru) and (bst)	USPAT; US-PGPUB	2002/10/03 16:12
-	0	438/FOR.212.ccls. and (ruthenium or ru) and BST	EPO; JPO; DERWENT	2002/10/03 17:03
-	0	438/FOR.220.ccls. and (ruthenium or ru) and BST	EPO; JPO; DERWENT	2002/10/03 17:03
-	0	438/FOR.212.ccls. and (ruthenium or ru)	EPO; JPO; DERWENT	2002/10/03 17:03
-	0	438/FOR.220.ccls. and (ruthenium or ru)	EPO; JPO; DERWENT	2002/10/03 17:09
-	51	(ruthenium or ru) and BST	EPO; JPO; DERWENT	2002/10/03 17:09
-	22	((ruthenium or Ru) and ("nitrous oxide")) and BST	USPAT; US-PGPUB	2002/10/04 09:33
-	13596	(electrode or plate or node or capacitor) NEAR5 (oxidized or oxidize or oxidation or oxidizing)	USPAT; US-PGPUB	2002/10/04 11:38
-	1394	((electrode or plate or node or capacitor) NEAR5 (oxidized or oxidize or oxidation or oxidizing)) and ruthenium	USPAT; US-PGPUB	2002/10/04 11:39
-	273	((electrode or plate or node or capacitor) NEAR5 (oxidized or oxidize or oxidation or oxidizing)) and ruthenium and (438/\$.ccls.)	USPAT; US-PGPUB	2002/10/04 12:19
-	334	((lower or bottom) ADJ2 (electrode or plate)) SAME (plasma or treatment)) and ruthenium	USPAT; US-PGPUB	2002/10/04 18:13
-	1	("5,852,307").PN.	USPAT; US-PGPUB	2002/10/04 12:47
-	2192	(plug or concave or hole with oxide with nitride) and (ruthenium)	USPAT; US-PGPUB	2002/10/04 17:14
-	288	(plug or concave or hole with oxide with nitride) SAME (TiN or TiAlN) SAME (silicide)	USPAT; US-PGPUB	2002/10/04 17:14
-	74	((plug or concave or hole with oxide with nitride) SAME (TiN or TiAlN) SAME (silicide)) and ruthenium	USPAT; US-PGPUB	2002/10/04 17:14
-	24	(US-6455424-\$ or US-6255187-\$ or US-6159868-\$ or US-6010931-\$ or US-5668040-\$ or US-6091099-\$ or US-6281142-\$ or US-6274454-\$ or US-6265262-\$).did. or (US-20020022357-\$ or US-20010024852-\$ or US-20020102826-\$ or US-20020096745-\$ or US-20020076878-\$ or US-20010053058-\$ or US-20010052466-\$ or US-20010016382-\$ or US-20010006838-\$ or US-20010043453-\$ or US-20020037624-\$ or US-20020037630-\$ or US-20020022334-\$ or US-20010029113-\$ or US-20010009282-\$).did.	USPAT; US-PGPUB	2002/10/07 13:43
-	3	((US-6455424-\$ or US-6255187-\$ or US-6159868-\$ or US-6010931-\$ or US-5668040-\$ or US-6091099-\$ or US-6281142-\$ or US-6274454-\$ or US-6265262-\$).did. or (US-20020022357-\$ or US-20010024852-\$ or US-20020102826-\$ or US-20020096745-\$ or US-20020076878-\$ or US-20010053058-\$ or US-20010052466-\$ or US-20010016382-\$ or US-20010006838-\$ or US-20010043453-\$ or US-20020037624-\$ or US-20020037630-\$ or US-20020022334-\$ or US-20010029113-\$ or US-20010009282-\$).did.) and (USP or PSG)	USPAT; US-PGPUB	2002/10/07 13:45
-	1431	(USG or PSG) same (concave or hole)	USPAT; US-PGPUB	2002/10/07 13:46
-	29	((USG or PSG) same (concave or hole)) and ruthenium	USPAT; US-PGPUB	2002/10/07 13:47
-	546	((USG or PSG) same (concave or hole)) and capacitor	USPAT; US-PGPUB	2002/10/07 13:52

-	526	((USG or PSG) same (concave or hole)) and capacitor) NOT ruthenium	USPAT; US-PGPUB	2002/10/07 13:49
-	117	((USG or PSG) same (concave or hole)) and (stacked ADJ3 capacitor)	USPAT; US-PGPUB	2002/10/07 13:57
-	95	((USG or PSG) same (concave or hole)) and (stacked ADJ3 capacitor)) and dram	USPAT; US-PGPUB	2002/10/07 14:53
-	1363	fluorosilicate	USPAT; US-PGPUB	2002/10/07 15:30
-	24	(US-6281142-\$ or US-6274454-\$ or US-6265262-\$ or US-6455424-\$ or US-6010931-\$ or US-5668040-\$ or US-6255187-\$ or US-6159868-\$ or US-6091099-\$).did. or (US-20010043453-\$ or US-20020037630-\$ or US-20020022334-\$ or US-20010029113-\$ or US-20010009282-\$ or US-20020037624-\$ or US-20010024852-\$ or US-20020022357-\$ or US-20020076878-\$ or US-20020102826-\$ or US-20020096745-\$ or US-20010053058-\$ or US-20010016382-\$ or US-20010052466-\$ or US-20010006838-\$).did.	USPAT; US-PGPUB	2002/10/14 15:48
-	6	((US-6281142-\$ or US-6274454-\$ or US-6265262-\$ or US-6455424-\$ or US-6010931-\$ or US-5668040-\$ or US-6255187-\$ or US-6159868-\$ or US-6091099-\$).did. or (US-20010043453-\$ or US-20020037630-\$ or US-20020022334-\$ or US-20010029113-\$ or US-20010009282-\$ or US-20020037624-\$ or US-20010024852-\$ or US-20020022357-\$ or US-20020076878-\$ or US-20020102826-\$ or US-20020096745-\$ or US-20010053058-\$ or US-20010016382-\$ or US-20010052466-\$ or US-20010006838-\$).did.) and (crystallize or crystallizing)	USPAT; US-PGPUB	2002/10/14 15:49
-	107	((anneal or annealing or thermal or thermally) WITH capacitor) and (ruthenium and bst)	USPAT; US-PGPUB	2002/10/14 16:42
-	11	((((anneal or annealing or thermal or thermally) WITH capacitor)) same (stabilize or stabilizing or stable)) and ruthenium and bst	USPAT; US-PGPUB	2002/10/14 16:44

L Number	Hits	Search Text	DB	Time stamp
-	216643	capacitor	USPAT; US-PGPUB	2002/10/02 11:50
-	1612	capacitor and (ruthenium)	USPAT; US-PGPUB	2002/10/02 12:44
-	680	((capacitor and (ruthenium)) and (plasma or ("N.sub.20" and "NH.sub.3"))	USPAT; US-PGPUB	2002/10/02 11:52
-	41	((capacitor and (ruthenium)) and ("N.sub.20" and "NH.sub.3"))	USPAT; US-PGPUB	2002/10/02 11:54
-	8	((capacitor and (ruthenium)) and ("N.sub.20" and "NH.sub.3")) and BST	USPAT; US-PGPUB	2002/10/02 11:54
-	117	capacitor and (ruthenium or ru) and (plasma ADJ2 treatment)	USPAT; US-PGPUB	2002/10/02 12:36
-	218	capacitor and ((electrode or Ru or ruthenium) SAME ("plasma treatment"))	USPAT; US-PGPUB	2002/10/02 12:46
-	7	capacitor and ((Ru or ruthenium) SAME ("plasma treatment"))	USPAT; US-PGPUB	2002/10/02 12:39
-	676	(capacitor and (ruthenium)) and plasma	USPAT; US-PGPUB	2002/10/02 12:44
-	20	capacitor and ((electrode or Ru or ruthenium) SAME ("plasma treatment")) and BST	USPAT; US-PGPUB	2002/10/02 12:47